



2018 Source Workshop

November 5-7, 2018
HiLASE, Prague, Czech Republic

First Call for Papers

This leading annual workshop focuses on the latest scientific and technical developments related to extreme ultraviolet (EUV) and soft X-ray sources. The workshop will provide a forum for researchers and end-users in the EUV and Soft X-ray light sources area to present their work and discuss a wide range of potential applications. In focus will be the generation of photons in this wavelength region, using laser-produced plasma (LPP), discharge-produced plasma (DPP), high-harmonic generation (HHG), free electron lasers (FEL), synchrotrons and innovative concepts. We also welcome papers describing applications of these sources in EUV lithography for scanner and metrology applications, microscopy, analytical instrumentation and for supporting scientific research in material and biological sciences. In addition to experimental studies, we encourage submission of theoretical and modeling papers.

This year, once again, we will organize a special session on lasers employed in the leading-edge chip manufacturing. This session will cover lasers that are used in LPP, DPP, XUV, FEL sources and in metrology applications. Our goal is to understand the status and requirements for these lasers and define areas where future work is needed. Additional special topics and complete list of topics for the workshop will be announced soon on our website www.euvlitho.com.

Abstracts of 200 words or fewer should be sent to abstracts@euvlitho.com by September 14, 2018. Student papers are highly encouraged. Please, indicate whether an oral or poster presentation is preferred and include each author's full name, e-mail address, affiliation and mailing address. Please, also include a brief biography and photograph of the presenting author, for inclusion in the abstract book. The workshop proceedings will be published online and made available to all. Proceedings of the previous workshop are available online at www.euvlitho.com.

For opportunities to sponsor the workshop, please contact Dr. Vivek Bakshi at vivek.bakshi@euvlitho.com.

Abstract Due Date
September 14, 2018
Submit abstract to
abstracts@euvlitho.com

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Venue

HiLASE, Prague - Dolni Brezany

Registration and Travel Info

Coming soon at
www.euvlitho.com

Organized by

